Photo Chemical Machining Institute

One Day Short Course

Fall Conference • October 3 - 7, 2010 • Pan Pacific Orchard Hotel • Singapore

"Photochemical Machining: What it is and how to control it"

Presented by Professor David Allen,
Professor of Microengineering, Cranfield University, UK

at
Nanyang Polytechnic, Singapore
on
Thursday October 7th, 2010

Syllabus
The Photochemical Machining (PCM) process is a multi-stage process involving photoresist imaging and chemical etching technology that requires strict control at all stages for the manufacturing of high quality products at competitive prices. The course considers the vast product range and the metals, photoresists and etchants used. Particular attention is paid to quality control of ferric chloride and cupric chloride etchants and the industrial etchant regeneration methods used to reduce process costs and comply with environmental legislation.

Language: The Short Course will be conducted in English but there will be some provision for English/ Mandarin translation.

Lecture room location: Lecture room details will follow delegate registration via PCMI.

Fees: Fees are payable via PCMI.

Members and First Time Attendees	US $500.00
Non Members	US $800.00

Schedule for Thursday October 7th 2010

0900-1030
Introduction to PCM, ferric chloride, cupric chloride and the role of photoresists

1030-1100
Coffee break

1100-1230
Ferric chloride etchant and how to monitor it

1230-1330
Luncheon

1330-1500
Environmental control and ferric chloride and cupric chloride regeneration

1500-1530
Tea break

1530-1630
Round table session for individual questions, summary and close